



Docket No.: N.C. 82,745

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#14A

11/8/02
MW

Applicants : Chrisey et al.
Appl. No. : 09/671,166
Filed : September 28, 2000
Title : MATRIX ASSISTED PULSED LASER EVAPORATION DIRECT
WRITE
Art Unit : 1763
Examiner : Karla A. Moore

Honorable Assistant Commissioner for Patents
Washington, DC 20231

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AMENDMENT

Sir:

In response to the Office Action mailed on May 3, 2002, the period for Response being until August 3, 2002, please amend the above-identified patent application as follows:

In the Specification:

Please replace the paragraph beginning at page 2, line 19, with the following rewritten paragraph:

A¹

-- In the direct writing technique known as "laser induced forward transfer" (LIFT), a pulsed laser beam is directed through a laser-transparent target substrate to strike a film of material coated on the opposite side of the target substrate. The laser vaporizes the film material as it absorbs the laser radiation and, due to the transfer of momentum, the material is removed from the target substrate and is redeposited on a receiving substrate that is placed in proximity to the target substrate. Laser induced forward transfer is typically used to transfer opaque thin films, typically metals, from a pre-coated laser transparent support, typically glass, SiO₂, Al₂O₃, SrTiO₃, etc., to the receiving substrate. Various methods of laser-induced forward transfer are

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